

1731  
*John*



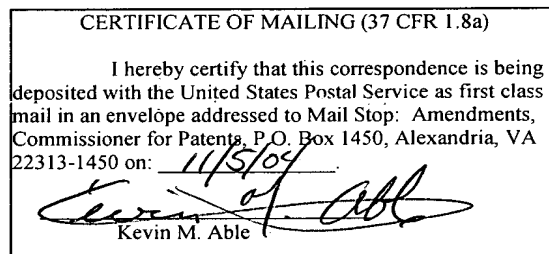
**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

Appl. No. : 10/027,282  
Applicant : House, Keith L, et al.  
Filed : 12/21/2001  
Title : Plasma Chemical Vapor Deposition Methods And Apparatus

TC/A.U. : 1731  
Examiner : Hoffmann, John M

Docket No. : SP01-347

Mail Stop: Amendments  
Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450



**AMENDMENT**

Sir:

In response to the Office action of August 6, 2004, please amend the above-identified as follows:

**Amendments to the Claims** are reflected in the listing of claims which begins on page 2 of this paper.

**Remarks/Arguments** begin on page 5 of this paper.